

Supplementary Information for

## Hybrid graphene/amorphous carbon films with tadpole-like structures for high-performance photovoltaic applications

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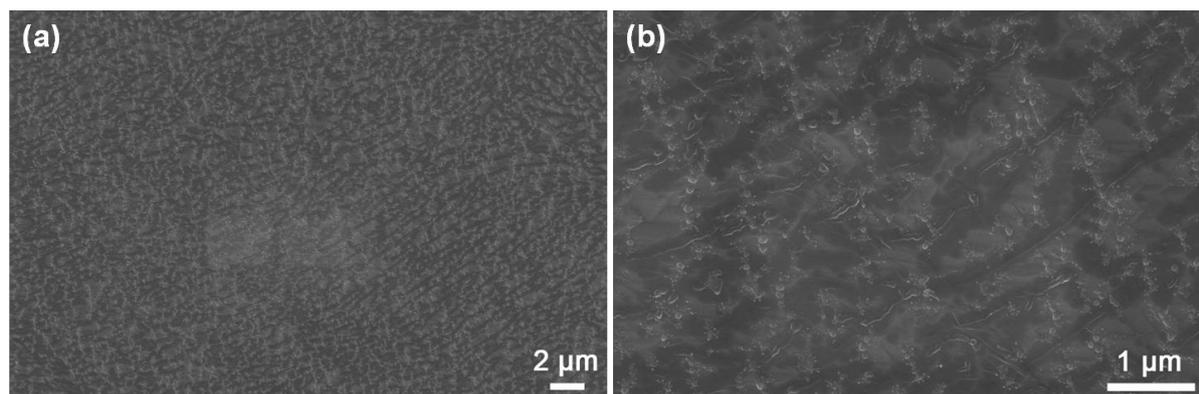
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### Figures:

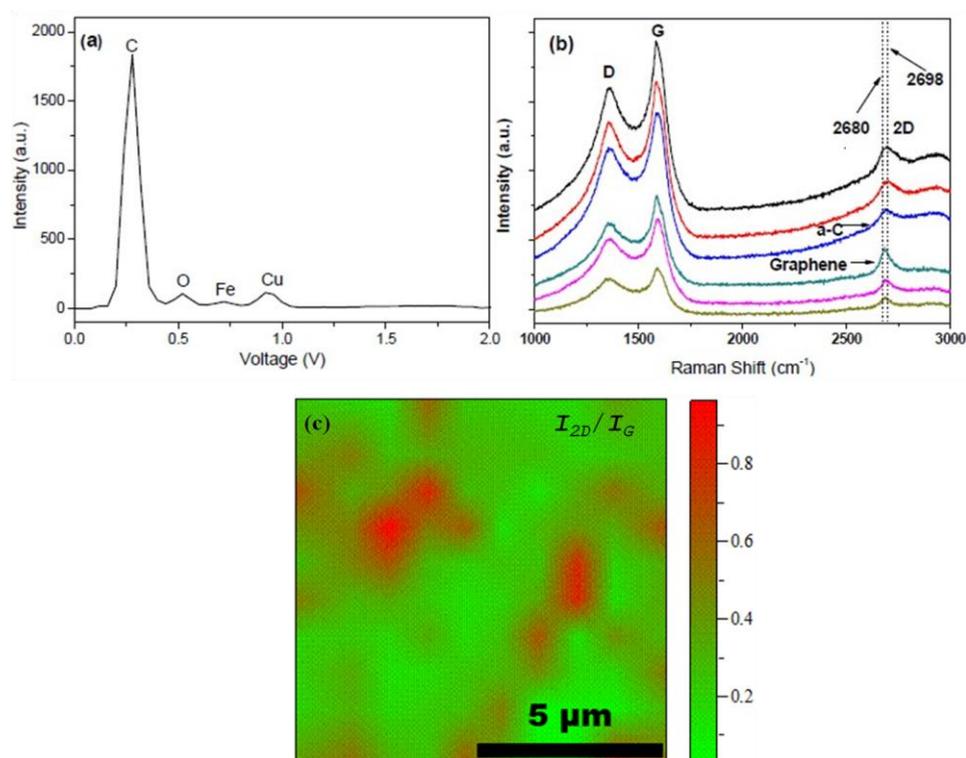


**Fig. S1** Typical SEM images of the G/a-C film at different magnifications (a) 10,000 $\times$  and (b) 50,000 $\times$ , showing many agglomerates on the surface.

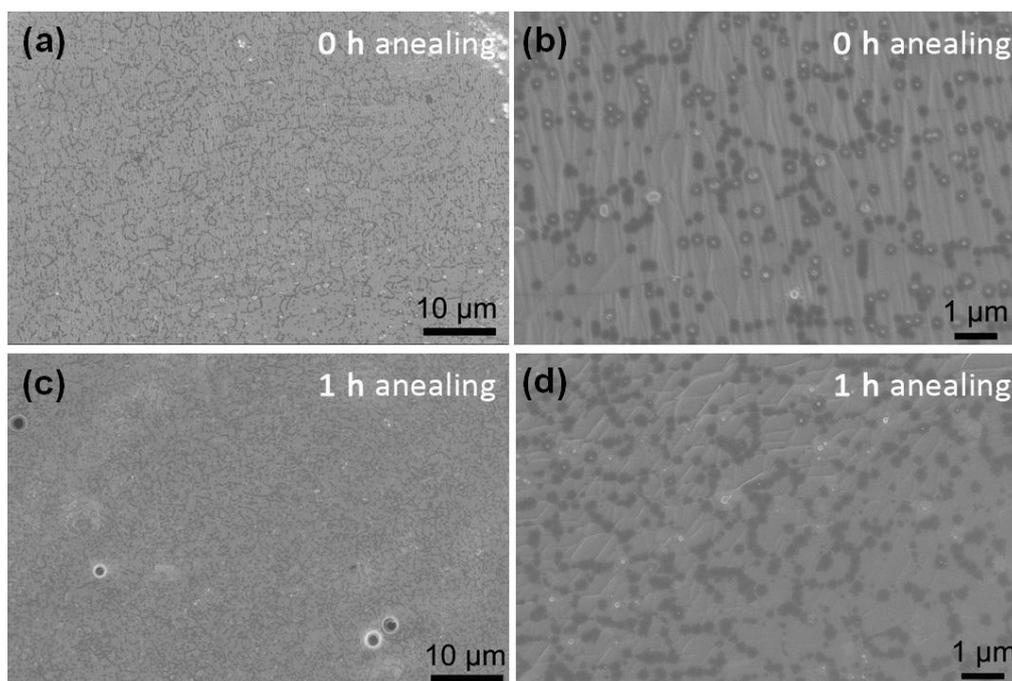
As shown in Figure S2a, the sample contains only carbon without other elements. The peak of Cu in the EDS can be attributed to the TEM grids. The presence of O can be attributed to the exposure of the samples in the air atmosphere.<sup>1</sup> Stainless steel mesh were used to transfer the G/a-C films from FeCl<sub>3</sub> solution to deionized water. Minor amount of Fe might come from FeCl<sub>3</sub> or stainless steel used during the G/a-C film transferring process. Thus, it is confirmed that agglomerates on the films are mainly composed of carbon. Raman spectra were carried out by randomly selecting six spots in the G/a-C film, as shown in the Figure S2b. All of the spectra consist of three peaks at 1350, 1590, and 2700 cm<sup>-1</sup>, which correspond to D-band, G-band and 2D-band, respectively. The position of the 2D-band is different at these six spots, which might be attributed to doping, defects or structural

difference.<sup>2,3</sup> In addition, the  $I_{2D}/I_G$  ratio and the full width at half maximum (FWHM) of 2D-band can be used to distinguish graphene and amorphous carbon.<sup>3,4</sup> One spectrum (green colour) has a  $I_{2D}/I_G$  of  $\sim 0.6$ , and a FWHM of  $\sim 70\text{ cm}^{-1}$ , showing the Raman spectrum feature of multilayer graphene.<sup>2</sup> One spectrum (blue colour) has a  $I_{2D}/I_G$  of  $\sim 0.15$ , and a FWHM of  $\sim 80\text{ cm}^{-1}$ , showing the Raman spectrum feature of amorphous carbon.<sup>3</sup>

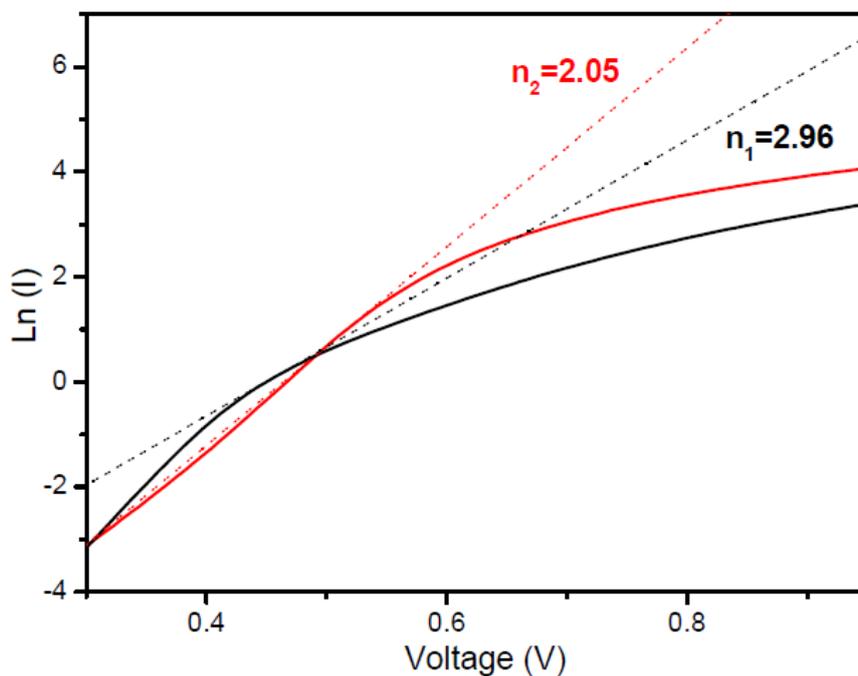
In order to further investigate the homogeneity of the G/a-C films, Raman mappings were acquired on a  $10\text{ }\mu\text{m} \times 10\text{ }\mu\text{m}$  area of G/a-C film, as shown in Figure S2c. Most of the scrutinized area within the G/a-C film exhibits  $I_{2D}/I_G \leq 0.4$ , while other area showing  $I_{2D}/I_G \geq 0.8$ . Based on the Raman spectra and Raman mapping of the carbon films, we can see that the films are hybrid multilayer graphene and amorphous carbon.



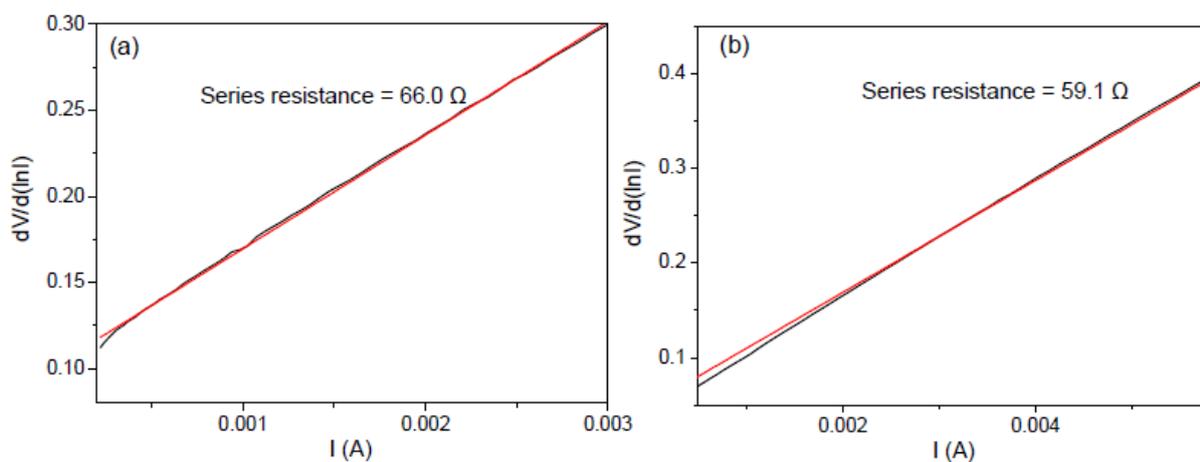
**Fig. 2** (a) Typical energy dispersive X-ray spectrum (EDS) of G/a-C films on Cu TEM grid, (b) Raman spectra of as-synthesized G/a-C films on SiO<sub>2</sub>/Si wafers, (c) 2D-band to G-band intensity ratio ( $I_{2D}/I_G$ ) mapping of G/a-C film on SiO<sub>2</sub>/Si substrate.



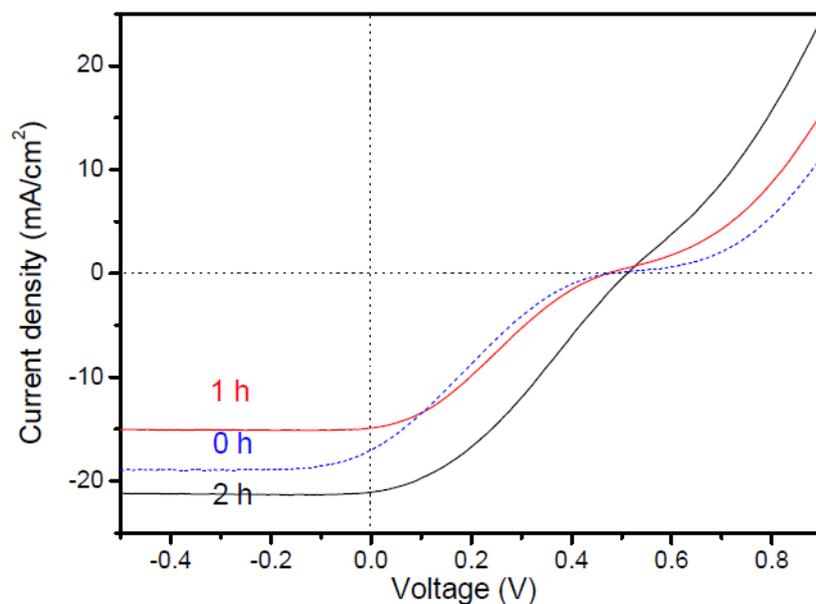
**Fig. S3** SEM images of control samples grown on Cu substrates with different annealing times. (a, b) 0 h, (c, d) 1 h.



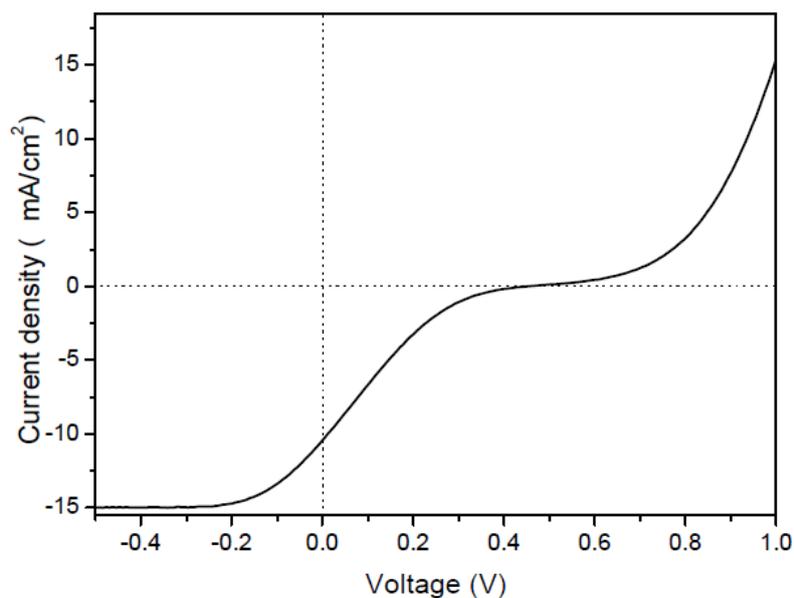
**Fig. S4** Napierian logarithm of dark current density ( $I$ ) versus voltage curve, showing the diode ideality factors before ( $n_1$ ) and after ( $n_2$ )  $\text{HNO}_3$  treatment, indicating the quality of Si-G/a-C Schottky junction is optimized.



**Fig. S5** The series resistance of Si-G/a-C Schottky junction solar cell before and after  $\text{HNO}_3$  treatment. (a) before  $\text{HNO}_3$  treatment, (b) after  $\text{HNO}_3$  treatment. ( $I$  is dark current, a liner fit of  $dV/d(\ln I)$  versus  $I$  gives the series resistance of Si-G/a-C Schottky junction solar cell.)



**Fig. S6** Light current density-voltage ( $J-V$ ) curves of the solar cells based on carbon film produced on Cu substrates with different annealing times.



**Fig. S7** Light current density-voltage ( $J$ - $V$ ) curves of the solar cell based on carbon film produced with an acetonitrile feed rate of 0.08 mL/min.

## Tables:

**Table S1** The photovoltaic properties of the intrinsic and HNO<sub>3</sub>-treated devices.

Conditions	$V_{oc}$ (mV)	$J_{sc}$ (mA/cm <sup>2</sup> )	FF	$\eta$ (%)
Pristine	510.1	21.0	34.1	3.66
HNO <sub>3</sub> -1min	547.8	20.5	51.0	5.73
HNO <sub>3</sub> -2min	547.8	20.2	52.4	5.78
HNO <sub>3</sub> -3min	547.8	20.2	53.2	5.90
HNO <sub>3</sub> -4min	555.3	20.0	53.4	5.92
HNO <sub>3</sub> -5min	555.3	20.0	53.5	5.95
HNO <sub>3</sub> -6min	555.3	20.3	53.5	6.03
HNO <sub>3</sub> -7min	555.3	20.4	53.5	6.05
HNO <sub>3</sub> -8min	555.3	20.3	53.8	6.07
HNO <sub>3</sub> -9min	555.3	20.2	53.6	6.01
HNO <sub>3</sub> -10min	555.3	20.3	53.4	6.03
HNO <sub>3</sub> -11min	555.3	20.3	54.0	6.07
HNO <sub>3</sub> -12min	555.3	20.2	53.5	5.99

**Table S2** The photovoltaic properties of the HNO<sub>3</sub>-treated devices after being exposed in air for different timescales.

Time after HNO <sub>3</sub> treatment (h)	$V_{oc}$ (mV)	$J_{sc}$ (mA/cm <sup>2</sup> )	FF	$\eta$ (%)
0	555.3	20.3	54.0	6.07
0.5	540.2	20.4	49.9	5.50
1	540.2	20.5	49.5	5.48
4	532.7	21.2	47.2	5.33
12	540.2	21.3	45.8	5.26
24	532.7	20.4	46.6	5.05
48	525.1	20.1	44.4	4.70
96	510.1	20.1	40.9	4.20
192	517.6	18.0	41.3	3.85

## References:

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